Controlling Crystal Structure and Oxidation State in Molybdenum Nitrides through Epitaxial Stabilization

Hongmei Luo,*,† Guifu Zou,‡ Haiyan Wang,§ Joon Hwan Lee,§ Yuan Lin,⊥ Huisheng Peng,# Qianglu Lin,† Shuguang Deng,† Eve Bauer,‡ T. Mark McCleskey,‡ Anthony K. Burrell,‡ and Quanxi Jia†,*

†Department of Chemical Engineering, New Mexico State University, Las Cruces, New Mexico 88003
‡Materials Physics and Applications Division, Los Alamos National Laboratory, Los Alamos, New Mexico 87545
§Department of Electrical and Computer Engineering, Texas A&M University, College Station, Texas 77843
⊥State Key Lab of Electronic Thin films and Integrated Devices, University of Electronic Science and Technology of China, Chengdu, Sichuan 610054, P. R. China
#Key Laboratory of Molecular Engineering of Polymers of Ministry of Education, Department of Macromolecular Science, Fudan University, Shanghai 200433, P. R. China
Figure S1. XRD patterns θ-2θ logarithmic scale of hexagonal MoN film on Al$_2$O$_3$ substrate (left) and cubic Mo$_2$N film on STO substrate (right).

Figure S2. AFM images of hexagonal MoN film on Al$_2$O$_3$ substrate (left) and cubic Mo$_2$N film on STO substrate (right). (1 µm × 1 µm)